ABSTRACT

In order to improve a processing efficiency of a plasma processing apparatus in which each of a plurality of source gas supply paths includes a first valve configured to open and close the source gas supply path, a second valve disposed on an upstream side of the first valve, a flow rate regulator disposed between the first valve and the second valve and configured to regulate a flow rate of a source gas flowing in the inner portion of the source gas supply path, and a connection unit between the source gas supply path and an inert gas supply path in which an inert gas is supplied to the inner portion connected at a position between the second valve and the flow rate regulator, in inspection of the plurality of source gas supply paths, a first inspection step of, for each of the plurality of source gas supply paths, sequentially determining presence or absence of a leakage in the first valve on the source gas supply path using a flow rate of the inert gas passing through the flow rate regulator on the source gas supply path in a state in which the first valve is closed in each of the plurality of source gas supplying paths and the inert gas is supplied from the inert gas supplying path, and a second inspection step of, for each of the plurality of source gas supply paths, supplying the inert gas from the inert gas supply path connected to the source gas supplying path in a state in which the first and second valves are closed and

detecting the leakage of the first valve on the source gas supply path using a change amount of a pressure of the inert gas supplied to the inert gas supply path if it is not determined in the first inspection step that there is a leakage in the first valve are performed.